

Amendments to the Specification

Please replace the paragraph at p. 11, ll. 27 – 33 with the following rewritten paragraph:

A

An optional remote plasma cleaning system **40** 140 is provided to periodically clean deposition residues from chamber components. The cleaning system includes a remote microwave or RF plasma generator 106 that creates a plasma from a cleaning gas source 98 such as molecular fluorine, nitrogen trifluoride, other fluorocarbons or equivalents, in a reactor cavity 108. The reactive species resulting from this plasma are conveyed to the chamber interior through cleaning gas feed port 110 via applicator tube 112.